Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 1/5

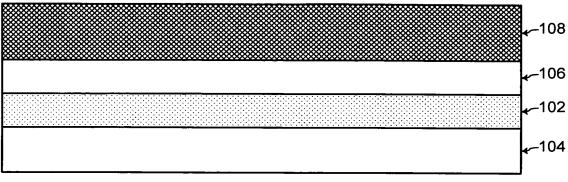


FIG. 1 (Prior Art)

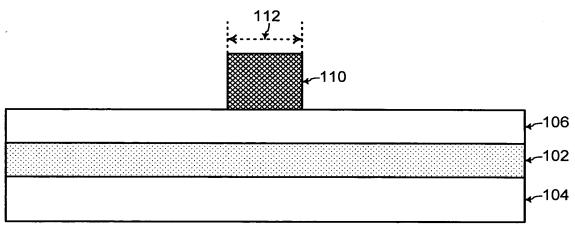


FIG. 2 (Prior Art)

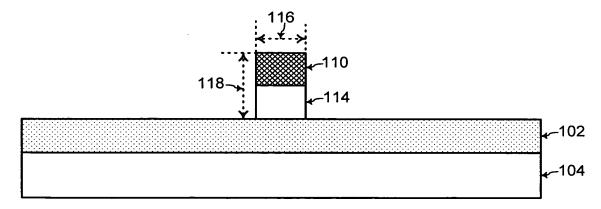


FIG. 3 (Prior Art)

<u>7</u>500 Unit(s) for Etching Mask Structure(s) Photolithography Unit 242 **Deposition Unit Photoresist** 218 214 Rigid Organic Under-Layer Deposition Unit Unit for Etching IC Material 210 Solution for Photoresist Development FIG. 4 238 220 **Deposition Unit** Hard-mask 206 Unit for Etching Hard-mask Layer Rigid Organic Under-Layer Unit for Etching 226 234 204

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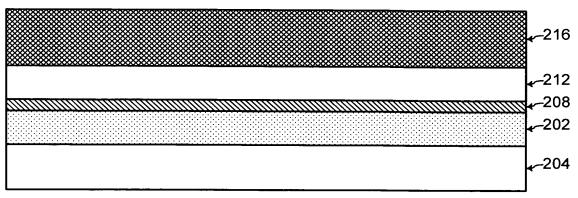


FIG. 5

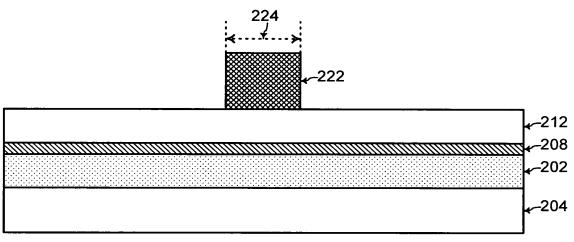


FIG. 6

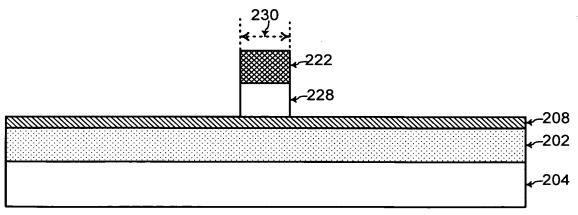
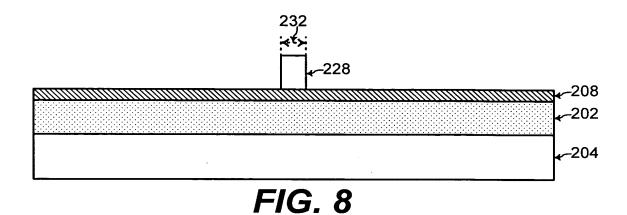
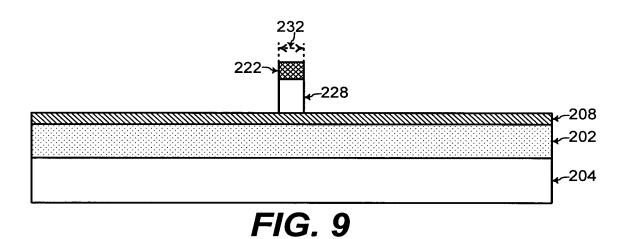
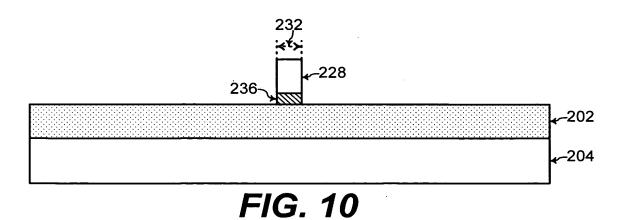


FIG. 7

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